

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	("6737305").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/10 14:07
L2	1639	(substrate or semiconductor or wafer) and silicon and CVD and flux and ("RF" or "radio frequency")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:09
L3	353	(substrate or semiconductor or wafer) and silicon and CVD and flux and ("RF" or "radio frequency") and angstrom and deposition and ratio	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:10
L4	5	(substrate or semiconductor or wafer) and silicon and CVD and (flux near ratio) and ("RF" or "radio frequency") and angstrom and deposition	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:15
L5	5	(substrate or semiconductor or wafer) and silicon and CVD and (flux near ratio) and ("RF" or "radio frequency") and angstrom and deposition and (H sub 2/SiH sub 4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:32
L6	3	(substrate or semiconductor or wafer) and silicon and CVD and (flux near ratio) and pressure and "radio frequency" and deposition and angstrom	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:33
L7	5	(substrate or semiconductor or wafer) and silicon and CVD and (flux near ratio) and pressure and "radio frequency"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/10 14:33